Tide: TWO MASK PHOTORESIST EXPOSURE PATTERN FOR DENSE AND ISOLATED REGIONS

REGIONS
Inventor(s): Ramkumar SUBRAMANIAN, et al.
DOCKET NO.: 039153-0381

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FIG. 1A PRIOR ART

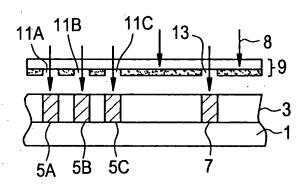


FIG. 1B PRIOR ART

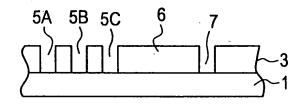
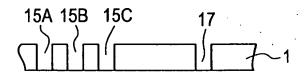


FIG. 1C PRIOR ART



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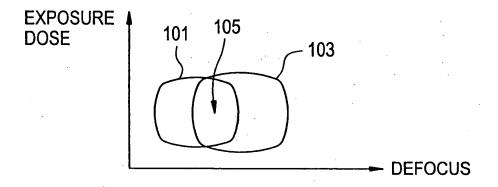
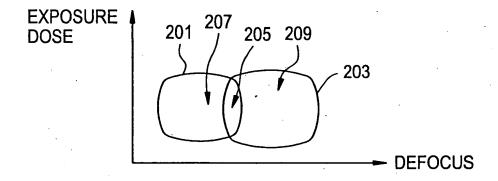
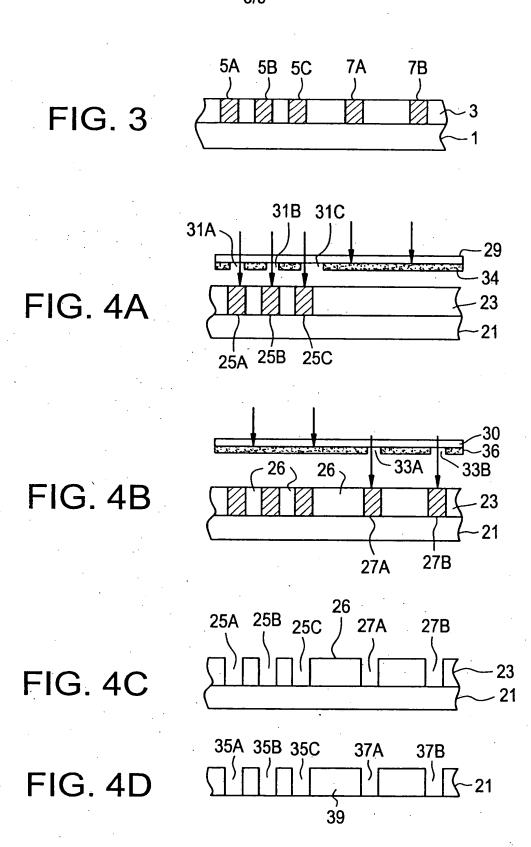


FIG. 2B







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FIG. 5A

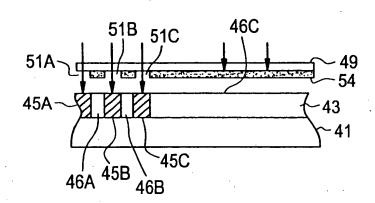


FIG. 5B

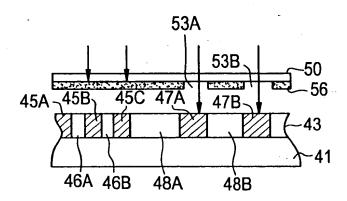


FIG. 5C

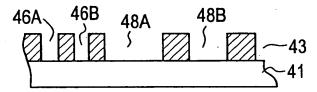
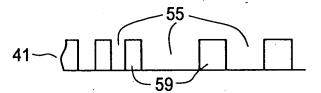


FIG. 5D



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FIG. 6

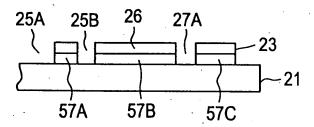
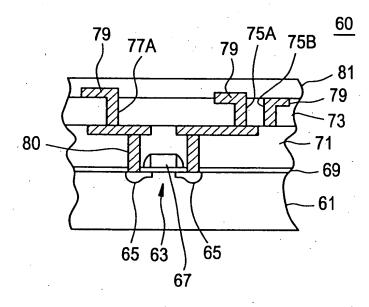


FIG. 7



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